

Segregation to creep-induced planar faults in Ni-base SX superalloys

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Introduction: Ni-base SX Superalloys



Application

• Fabrication: Bridgman process • γ / γ' microstructure



1.0

6.4

Bal.

https://www.theengineer.co.uk/
Frontiers of Mechanical Engineering 13.1 (2018): 3-16.

9.7

6.4

0.1

2.9

0.6

6.5

5.5

weight-%



Motivation

- Karlsruhe Institute of Technology
- If creep deformation behaviors and elemental segregation at 750 °C / 250 MPa are different with respect to different creep time (1% and 2%).



^[3] Annu. Rev. Mater. Res. 51 (2021): 209-240.

- L Dislocation
- $- \gamma / \gamma'$ interface
- 💳 Planar defect
- Segregation to crystal defects
- Dislocation processes and microstructural evolution
- --- {111} trace
- Partial dislocation
- ρ_{\perp} Dislocation density
- **PPF** Planar fault density
 - Cottrell atmosphere





Experimentals





- Double shear creep test
- Shear system: [112](111)
- Creep regime: 750 °C / 250 MPa
- Schmid factor: 1 with slip system $[11\overline{2}](111)$
- Creep time of 1%: 13.2 h; 2%: 35.5 h.





Creep induced planar faults in plane



STEM-BF images















[3] Annu. Rev. Mater. Res. 51 (2021): 209-240.

 $[1\overline{1}0]$



Creep induced planar faults edge on









Creep induced CESF of 2%

Trailing dislocation

A pair of leading dislocations



Stacking faults



EDX of CESF and leading dislocations of 2%





Shear mechanism of CESF of 2%







EDX of S(C)ESF of 1%







Conclusion



Creep microstructure of Ni-base SX superalloys which were deformed at 750 °C and 250 MPa to plastic strains 1% and 2% with shear system [11-2](111) are analyzed:

- Stacking faults (SESF/CESF) examined are enriched with γ -stabilizers—Cr and Co accompanied by a simultaneous depletion of γ' -stabilizers Ni and Al.
- The shearing process of CESF are experimentally observed:

 $1/2[\overline{1}01] + 1/2[0\overline{1}1] = 1/6[\overline{11}2] + CESF + 1/6[\overline{11}2] + 1/6[\overline{11}2]$

Cottrell cloud around a pair of leading dislocations of CESF hinders the movement of leading dislocations.



Acknowledgment









Thank you for your attention!

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